



IFW

In re the Application of) Confirmation No. 7016
ICHIMURA et al) Examiner: JOHNSON, Connie P.
Serial No.: 10/520,106) Art Unit: 1752
Filed: January 3, 2005)

For: ACTIVE RAY SENSITIVE RESIN COMPOSITION, ACTIVE ENERGY RAY

SENSITIVE FILM AND METHOD FOR FORMING PATTERN USING THE FILM

AMENDMENT & RESPONSE TO OFFICE ACTION OF MARCH 8, 2007

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Please amend the captioned application as follows: